

APPLICATION NUMBER	10/614,716
FILING DATE	07 July 2003
FIRST NAMED INVENTOR	Sreenivasan et al
GROUP ART UNIT	1722
EXAMINER NAME	Emmanuel S. Luk
ATTORNEY DOCKET NUMBER	P90-32V30

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EL	G7	Translation of Japanese Patent 61-40845, 2/1/1986	
EL	G8	Translation of Japanese Patent 02-248480, 10/1/1990	
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EL	G10	Translation of Japanese Patent 09-278490, 10/1/1997	
EL	G11	Abstract of Japanese Patent 03-090345, 4/1/1991	
EL	G12	Abstract of Japanese Patent 09-278490, 10/1/1997	
EL	G13	BIEN ET AL., Characterization of Masking Materials for Deep Glass Micromachining, J. Micromech. Microeng. 13 pp. S34-S40 1/1/2003	
EL	G14	BRITTEN ET AL., Multiscale, Multifunction Diffractive Structures We Etched into Fused Silica for High-Laser Damage Threshold Applications, Applied Optics, Vol. 37, No. 30 10/20/1998	
EL	G15	FLETCHER ET AL., Microfabricated Silicon Solid Immersion Lens, Journal of Microelectromechanical Systems, Vol. 10, No. 3 9/1/2001	

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EL	G16	KHANDAKER ET AL., Fabrication of Microlens Arrays by Direct Electron Beam Exposure of Photoresist, Pure Appl. Opt. 6, pp. 637-641 1/1/1997	
EL	G17	KIM ET AL., Replication Qualities and Optical Properties of UV-moulded Microlens Arrays, J. Phys. D: Appl. Phys. 36; pp. 2451-2456 1/1/2003	
EL	G18	KOBAYASHI ET AL., Batch Bulk-Micromachined High-Precision Metal-On-Insulator Microspires and Their Application to Scanning Tunneling Microscopy, J. Micromech. Microeng. 14; pp. S76-S81 1/1/2004	
EL	G19	KONIJN ET AL., Nanoimprint Lithography of Sub-100nm 3D Structures, Microelectronic Engineering 78-79; pp653-658 1/1/2005	
EL	G20	KUNNAVAKKAM ET AL., Low-cost, Low-loss Microlens Arrays Fabricated by Soft-Lithography Replication Process, Applied Physics Letters, Volume 82, Number 8 2/24/2003	
EL	G21	MANSELL ET AL., Binary-Optic Smoothing with Isotropic Etching, Applied Optics; Vol. 36, No. 20 7/10/1997	
EL	G22	WAHEED ET AL., Balancing Aerial Image Intensity for Alternating Aperture Phase Shift Masks Using an Isotropic Dry-Etch, Proceedings of SPIE Vol. 5130 4/18/2003	
EL	G23	SANO ET AL., Submicron Spaced Lens Array Process Technology for a High Photosensitivity CCD Image Sensor, IEEE IEDM Dig.; pp. 283-286 1/1/1990	
EL	G24	TSUKAMOTO ET AL., High Sensitivity Pixel Technology for a 1/4 inch PAL 430k pixel IT-CCD, IEE Custom Integrated Circuits Conference 1/1/1996	

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EC	G25	YONEDA ET AL., Translation of Japanese Patent 02-248480, Transparent Substrate with Water-Repellent and Antistaining Properties, and Structure Equipped Therewith 10/4/1990	
EC	G26	YONEDA ET AL., Translation of Japanese Patent 02-248480, Transparent Substrate Material with Water-Repellent and Anti-Staining Properties and Structure Equipped with Same 10/4/1990	

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